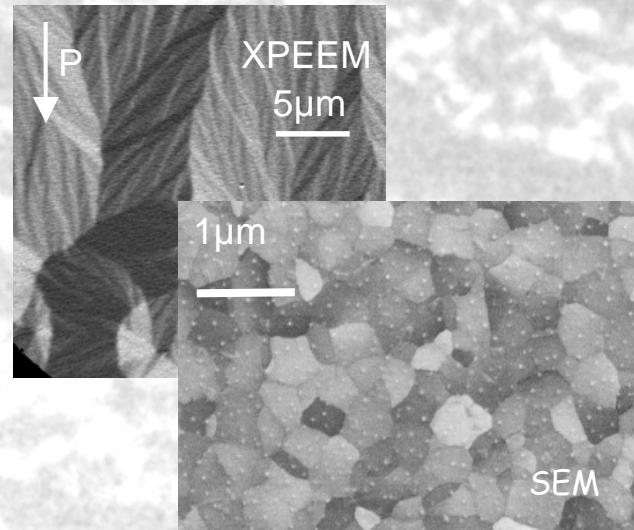
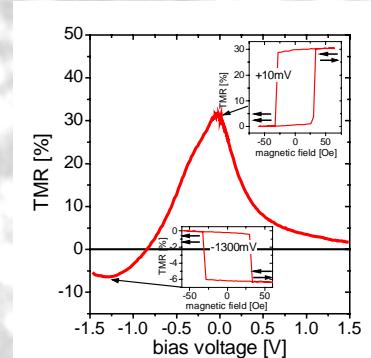


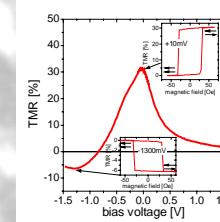
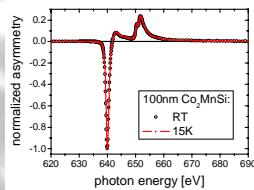
## *"Magnetic and chemical interface properties of magnetic tunnel junctions investigated by X-ray absorption spectroscopy"*



Jan Schmalhorst

*Thin Films and Nanostructures*  
Department of Physics  
Bielefeld University  
Germany





## Acknowledgements

...people:

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Bundesministerium für Bildung und Forschung (BMBF)  
Europäische Gemeinschaft (EU)  
Department of Energy (DOE)

# Motivation

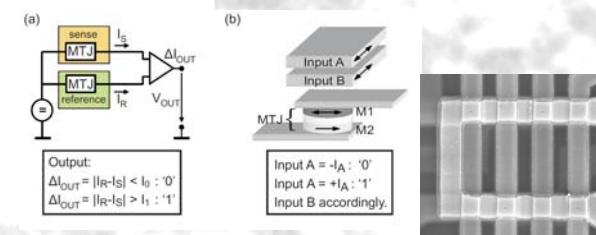
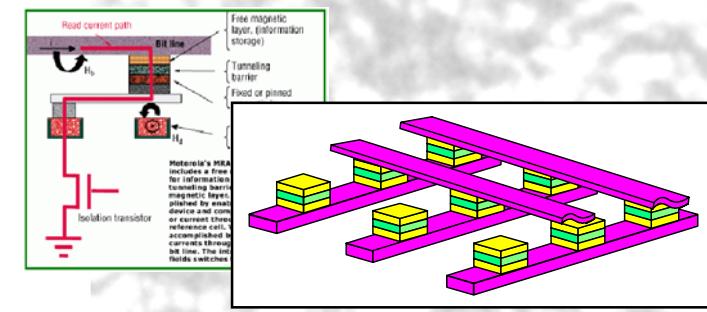
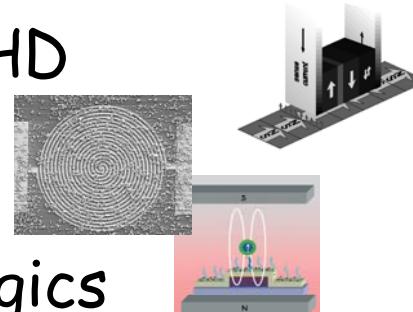
*Fundamentals of  
spin-electronics:*

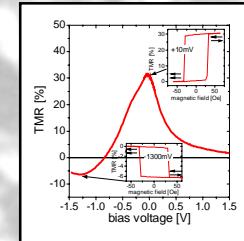
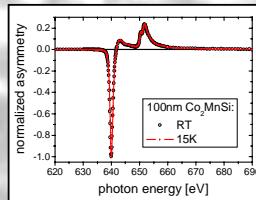
e<sup>-</sup>-charge + e<sup>-</sup>-spin = \$ + fun!



...some spin-electronic applications:

- non-volatile memory (MRAM)
- read-heads for HD
- sensors
- programmable logics
- ...





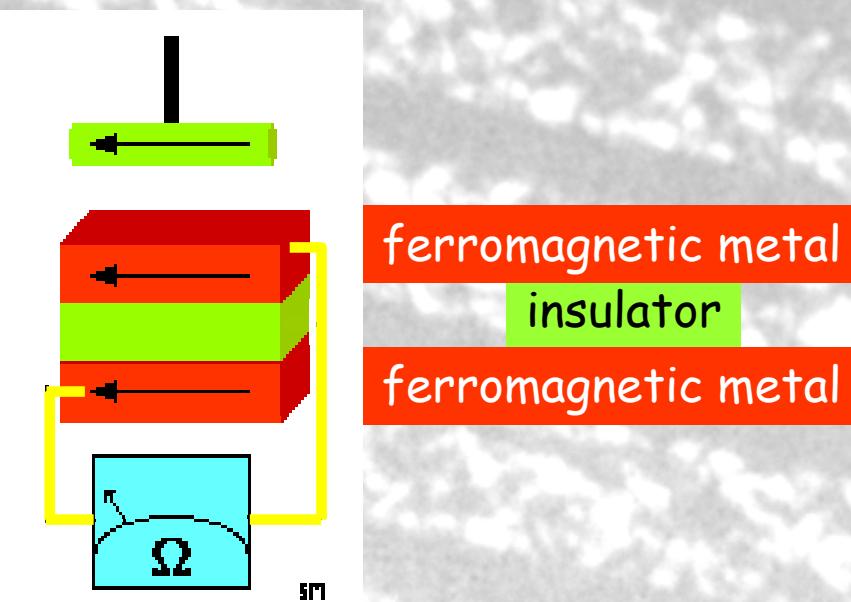
## Outline

- Basics of Magnetic Tunnel Junctions (MTJs)
- Brief history of Tunnel Magnetoresistance (the past and the future)
- Preparation and characterization techniques
- Some basic properties of the Heusler alloy  $\text{Co}_2\text{MnSi}$
- Results:
  - bulk properties of  $\text{Co}_2\text{MnSi}$  and other Heusler thin films
  - chemical and magnetic properties at  $\text{Co}_2\text{MnSi} / \text{Al-O}$  interface
  - characteristic transport properties of  $\text{Co}_2\text{MnSi}$  based MTJs compared with Co-Fe/Ni-Fe and Co-Fe-B based junctions
  - interpretation of transport properties on the base of XMCD/XAS investigations
- Conclusions

# Magnetic tunnel junction (MTJ)

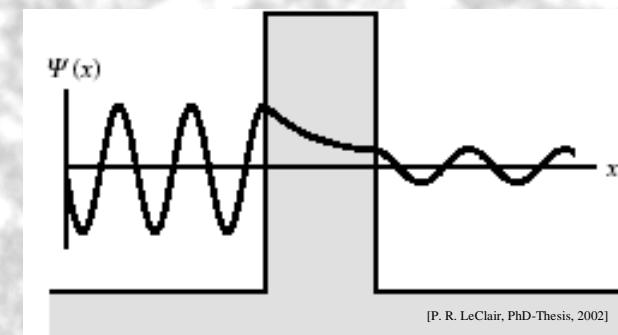
... a basic device for spin-electronics...

...the MTJ stack:



...fundamental physics:

QM tunnel effect  
(spin-polarized)

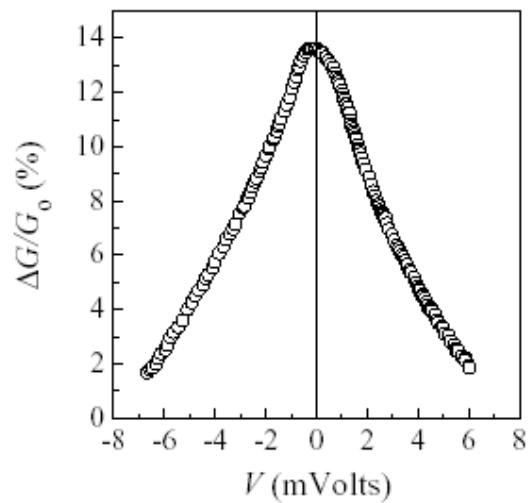


...tunnel magnetoresistance:

$$TMR = (R^{AP} - R^P) / R^P$$

...free particles can cross  
a potential barrier with  
finite probability!

## ...brief history of TMR in „conventional“ MTJs:



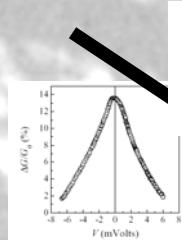
1975:  
M. Jullière  
Fe/Ge/Co: 14% @ 4.2K

$$TMR = \frac{2P_{eff}^{FM1}P_{eff}^{FM2}}{1 - P_{eff}^{FM1}P_{eff}^{FM2}}$$

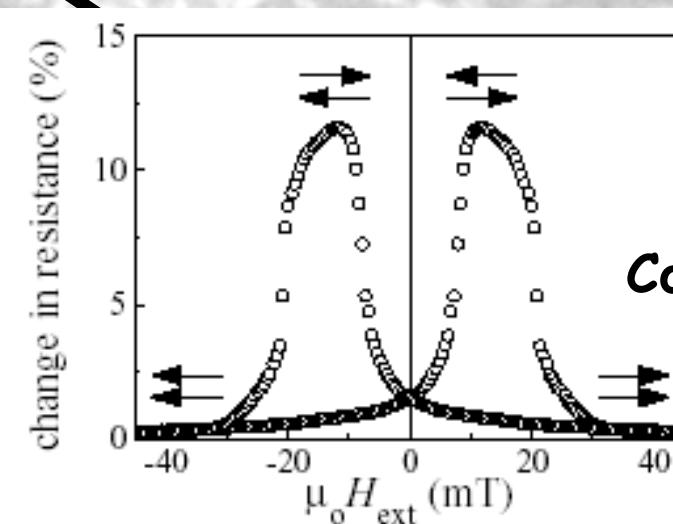
$$P_{eff} = \frac{Z^{\uparrow} - Z^{\downarrow}}{Z^{\uparrow} + Z^{\downarrow}}$$

time

## ...brief history of TMR in „conventional“ MTJs:



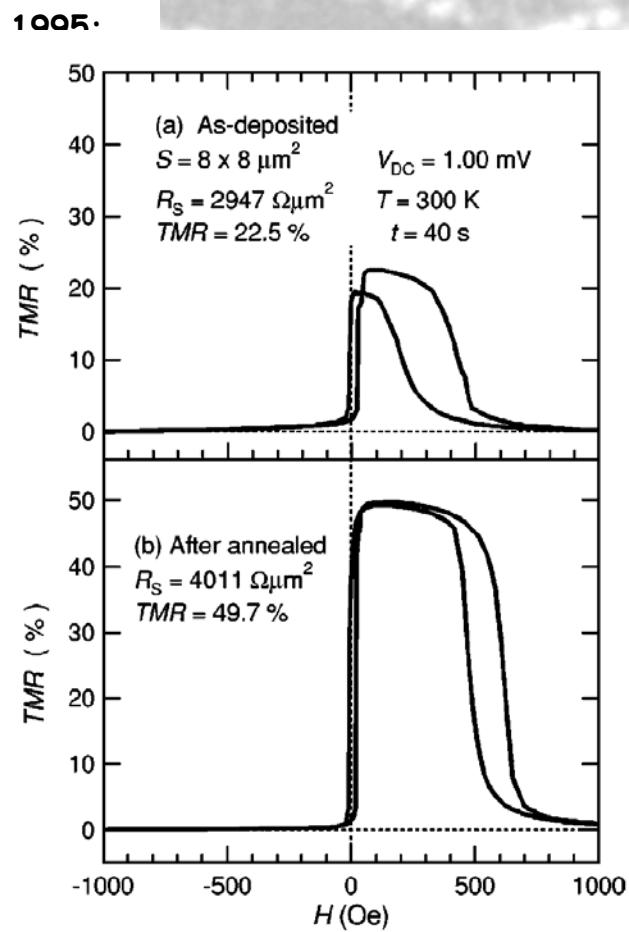
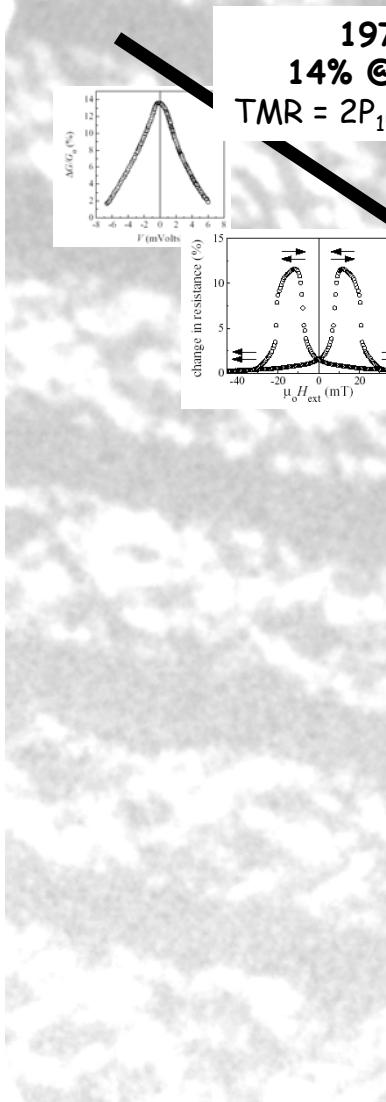
1975:  
14% @ 4.2K  
 $TMR = 2P_1P_2/(1-P_1P_2)$



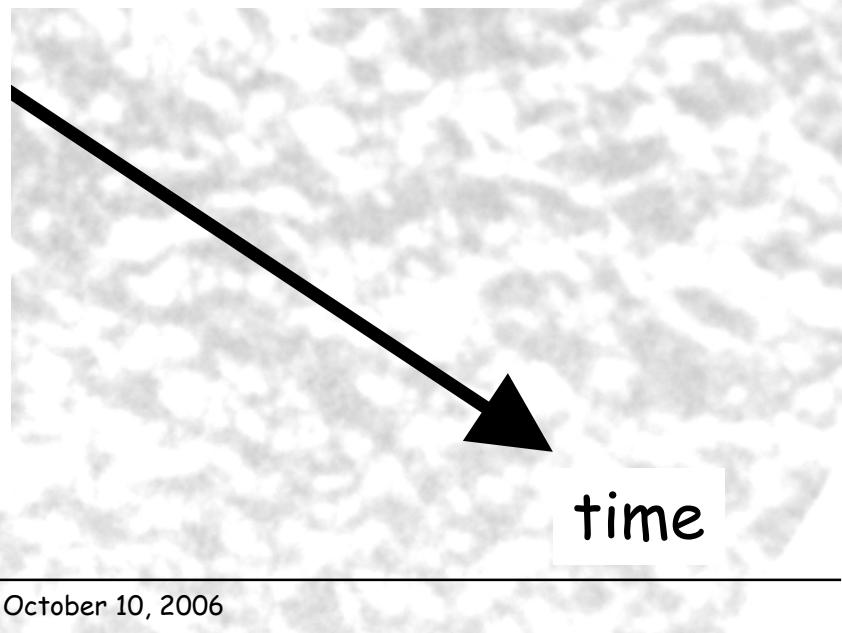
1995:  
J. Moodera  
 $Co/AI-O/Co$ : 12% @ RT

time

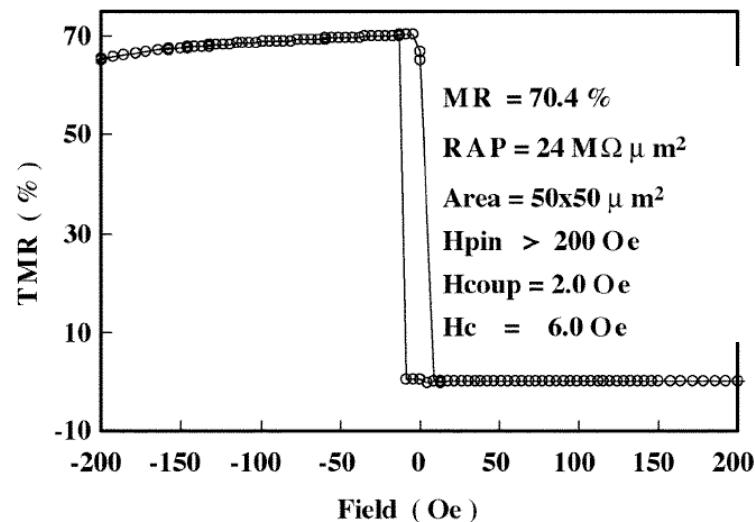
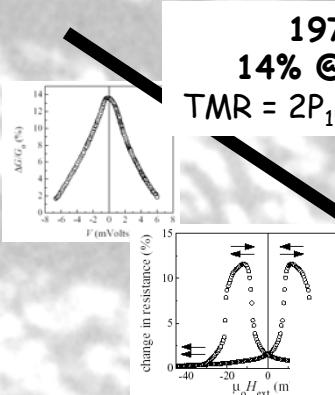
# ...brief history of TMR in „conventional“ MTJs:



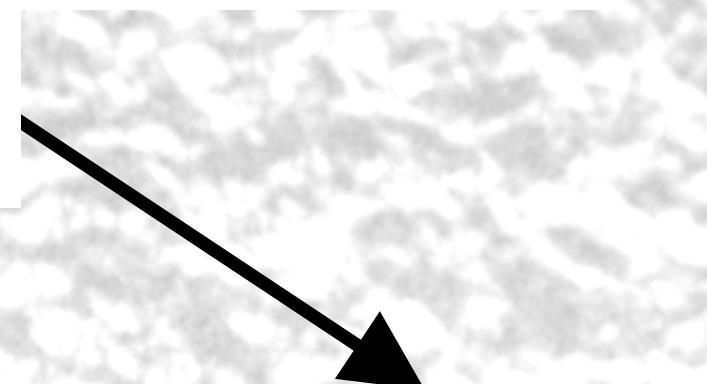
2000:  
X.-F. Han et al.  
Co-Fe/Al-O/Co-Fe:  
50% @ RT



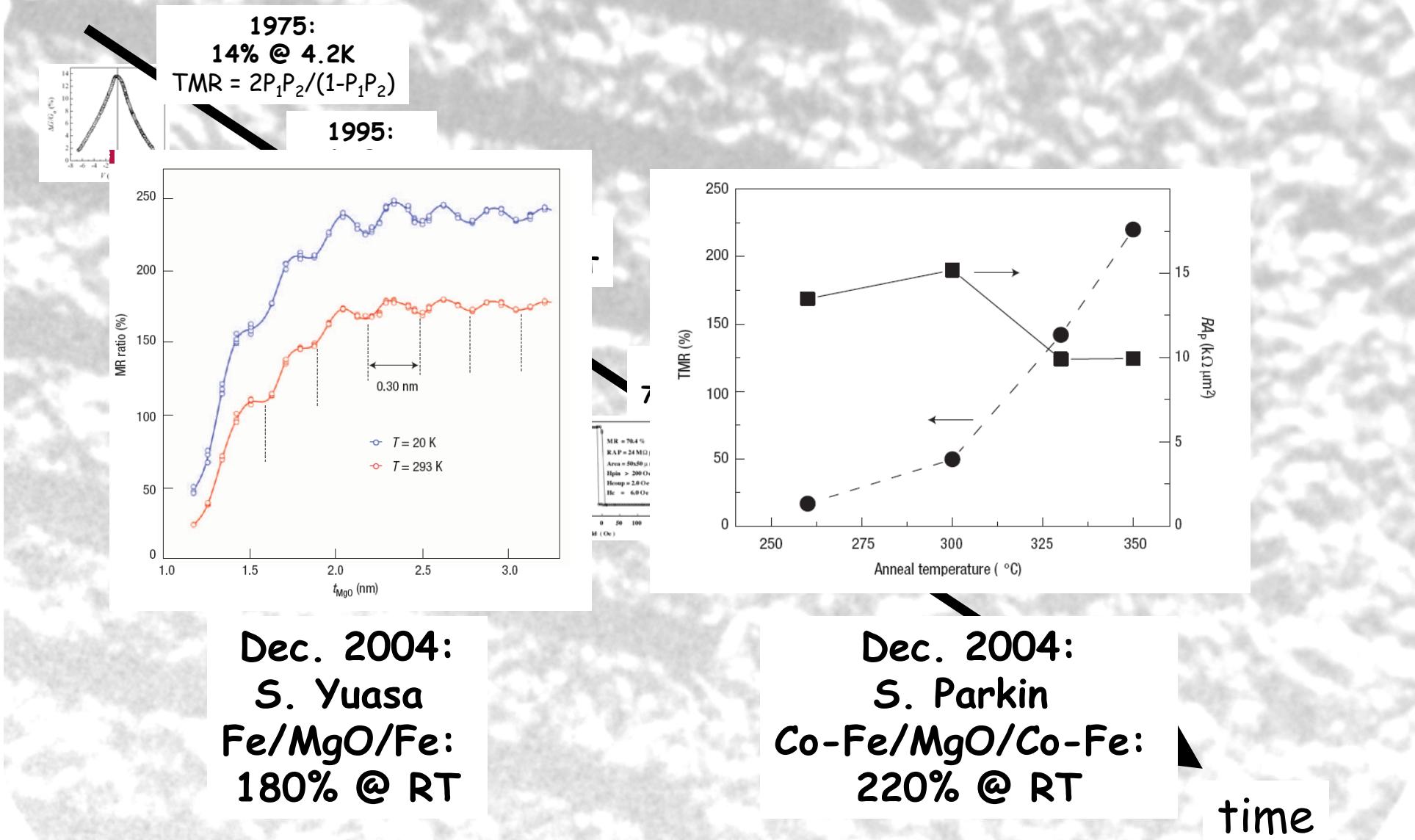
## ...brief history of TMR in „conventional“ MTJs:



Jan. 2004:  
D. Wang et al.  
Co-Fe-B/Al-O/Co-Fe-B:  
70% @ RT



# ...brief history of TMR in „conventional“ MTJs:



# ...brief history of TMR in „conventional“ MTJs:

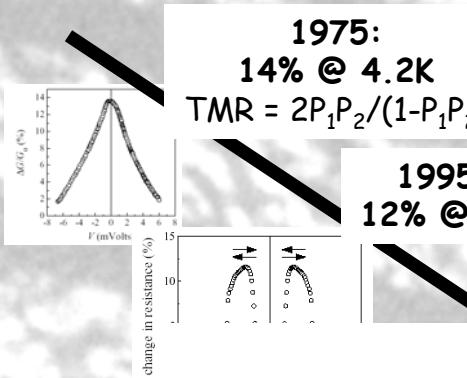
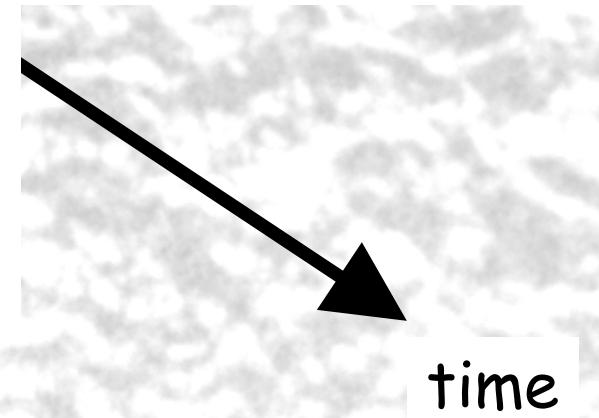


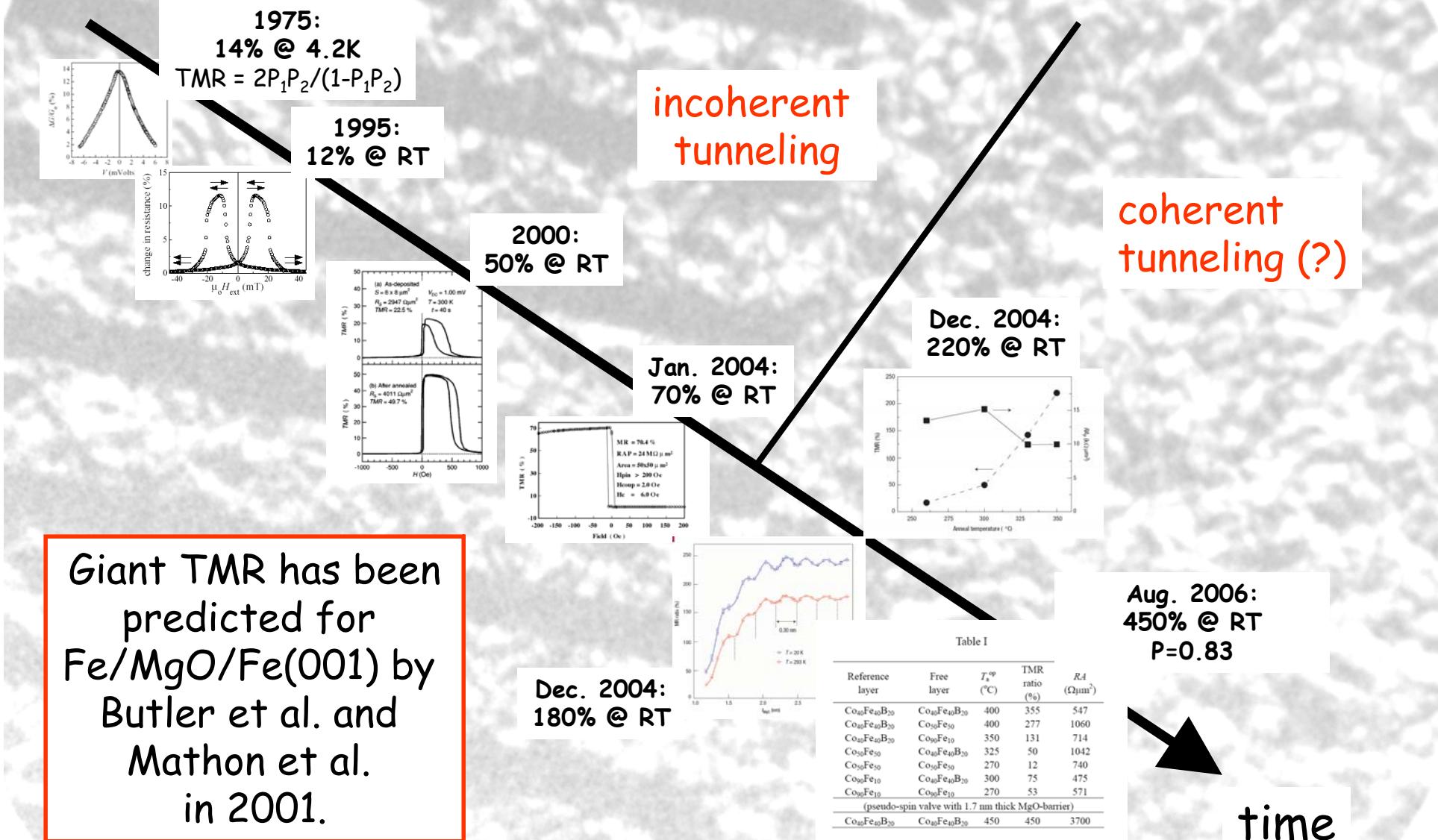
Table I

Reference layer	Free layer	$T_a^{\text{op}}$ (°C)	TMR ratio (%)	$RA$ ( $\Omega\mu\text{m}^2$ )
Co <sub>40</sub> Fe <sub>40</sub> B <sub>20</sub>	Co <sub>40</sub> Fe <sub>40</sub> B <sub>20</sub>	400	355	547
Co <sub>40</sub> Fe <sub>40</sub> B <sub>20</sub>	Co <sub>50</sub> Fe <sub>50</sub>	400	277	1060
Co <sub>40</sub> Fe <sub>40</sub> B <sub>20</sub>	Co <sub>90</sub> Fe <sub>10</sub>	350	131	714
Co <sub>50</sub> Fe <sub>50</sub>	Co <sub>40</sub> Fe <sub>40</sub> B <sub>20</sub>	325	50	1042
Co <sub>50</sub> Fe <sub>50</sub>	Co <sub>50</sub> Fe <sub>50</sub>	270	12	740
Co <sub>90</sub> Fe <sub>10</sub>	Co <sub>40</sub> Fe <sub>40</sub> B <sub>20</sub>	300	75	475
Co <sub>90</sub> Fe <sub>10</sub>	Co <sub>90</sub> Fe <sub>10</sub>	270	53	571
(pseudo-spin valve with 1.7 nm thick MgO-barrier)				
Co <sub>40</sub> Fe <sub>40</sub> B <sub>20</sub>	Co <sub>40</sub> Fe <sub>40</sub> B <sub>20</sub>	450	450	3700

Aug. 2006:  
S. Ikeda et al.  
Co-Fe-B/MgO/Co-Fe-B:  
450% @ RT  
P=0.83



# ...brief history of TMR in „conventional“ MTJs:



...not only coherent tunneling can increase the TMR:

Take Jullière's formula serious:  $TMR = 2P_1P_2/(1-P_1P_2)$

$\Rightarrow TMR = \infty$  for  $P_1 = P_2 = 1.0$  (half-metallic FM!)

Some materials predicted to be half-metallic:

- $CrO_2$
- $Fe_3O_4$
- manganites like  $La_{2/3}Sr_{1/3}MnO_3$ ,  $La_{2/3}Ca_{1/3}MnO_3$ , ...
- Heusler alloys like  $Co_2MnSi$ ,  $Co_2FeSi$ , ...

Recent results on Heusler alloy based MTJs (low T, small V):

- $Co_2MnSi$ (100) epitax./Al-O/Co-Fe:  $P_{Co2MnSi} = 0.89$  [1]
- $Co_2MnSi$ (110) tex./Al-O/Co-Fe:  $P_{Co2MnSi} = 0.66$  [2]
- $\{Co_2MnSi/Co_2FeSi\}_{10x}$ (110) tex./Al-O/Co-Fe:  $P_{Co2FeSi} = 0.74$  [3]

[1] Oogane et al., J. Phys. D: Appl. Phys. **39** (2006) 834

[2] J. Schmalhorst et al., Appl. Phys. Lett. **86** (2005) 152102

[3] D. Ebke et al., Appl. Phys. Lett., accepted (2006)

...the work presented today is published in:

- [A] J. Schmalhorst, S. Kämmerer, M. Sacher, G. Reiss, A. Hüttten, A. Scholl:  
"Interface structure and magnetism of magnetic tunnel junctions with  $\text{Co}_2\text{MnSi}$  electrode", *Phys. Rev. B* **70** (2004) 024426
- [B] J. Schmalhorst, M. D. Sacher, O. Schebaum, A. Thomas, G. Reiss, A. Hüttten, E. Arenholz: "Transport properties of magnetic tunnel junctions with  $\text{Co}_2\text{MnSi}$  electrode: influence of temperature-dependent interface magnetization and electronic band structure", *Phys. Rev. B*, submitted
- [C] J. Schmalhorst, M. D. Sacher, V. Höink, G. Reiss, A. Hüttten, D. Engel, A. Ehresmann: „Magnetic tunnel junctions with  $\text{Co}_2\text{MnSi}$  electrode: magnetic and chemical properties of the bulk and of the electrode / barrier interface”,  
*J. Appl. Phys.*, accepted
- [D] D. Ebke, J. Schmalhorst, N.-N. Liu, A. Thomas, G. Reiss, A. Hüttten: "Large tunnel magnetoresistance in tunnel junctions with  $\text{Co}_2\text{MnSi} / \text{Co}_2\text{FeSi}$  multilayer electrode",  
*Appl. Phys. Lett.*, accepted

# Why is the implementation of Heusler alloys in MTJs so challenging?

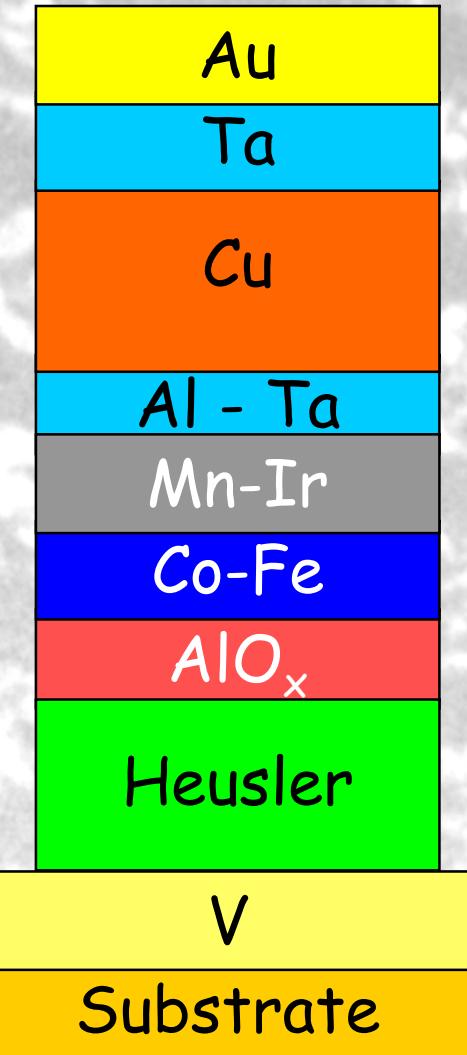
## MTJ:

- very sensitive to barrier-electrode interface
- thermal stability limited to typically 350°C

## sputtered Heusler alloy:

- half-metallicity usually very sensitive to atomic disorder
- thermal treatment at high T required to promote atomic order  
(e.g.  $\approx 450^\circ\text{C}$  for  $\text{Co}_2\text{MnSi}$ )

## ...typical layer stack of our Heusler based MTJs:



We need to know the transport properties of "full" junctions...

magnetoresistance:

$$R = R(V, T, H_{ex})$$

current-voltage-characteristic:

$$dj/dV = dj/dV (V, T, H_{ex})$$

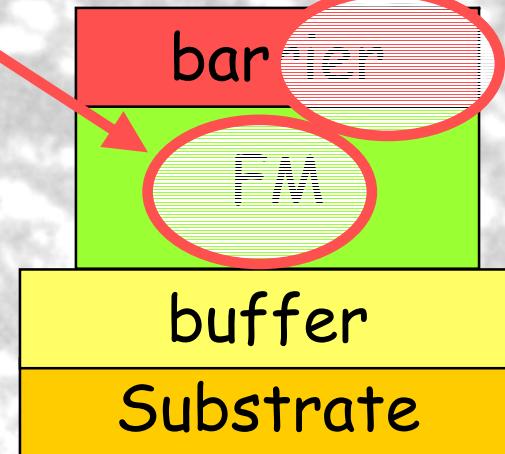
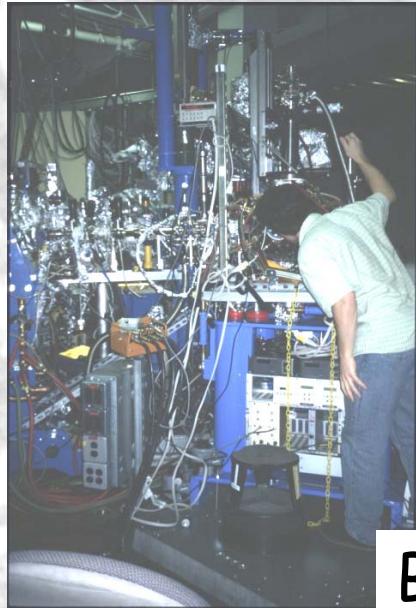
...and their structural and magnetic properties:

AGM, XRD, Auger depth profiling, **XMCD/XAS**

# Why do we apply XAS and XMCD to "half" junctions?

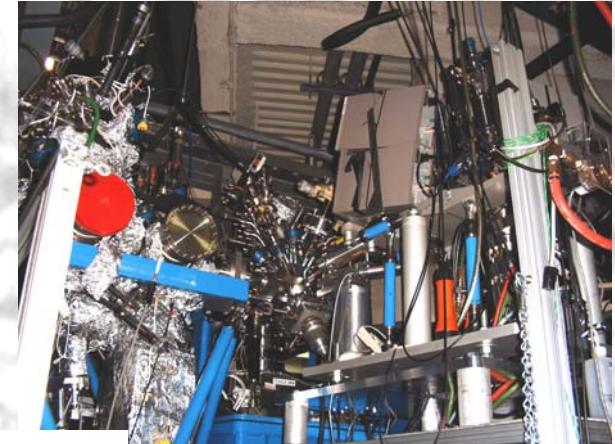
⇒ element specific chemical and magnetic properties  
of Heusler / barrier interface and Heusler bulk...

XAS / XMCD (FY)



BL 4.0.2

XAS / XMCD (TEY)



BL 7.3.1.1

# How do we fabricate our MTJs?

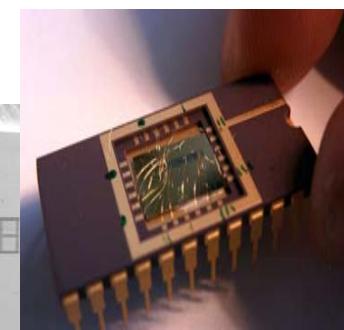
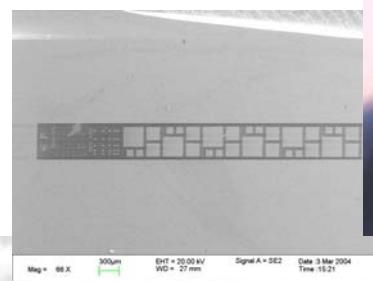
1) magnetron sputter deposition at  $<10^{-7}$  mbar (polycrystalline films)



2) in-situ and/or ex-situ annealing

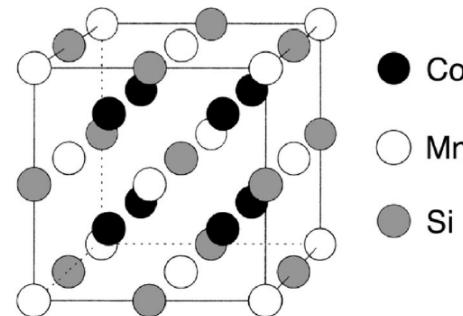


3) patterning / bonding



# ...some properties of the Heusler alloy $\text{Co}_2\text{MnSi}$ :

*Theory* [PRB 65 (2002) 184431,  
I. Galanakis, private communication]:



4x fcc:  
Mn: 0 0 0  
Si:  $\frac{1}{2} \frac{1}{2} \frac{1}{2}$   
Co:  $\frac{1}{4} \frac{1}{4} \frac{1}{4}, \frac{3}{4} \frac{3}{4} \frac{3}{4}$

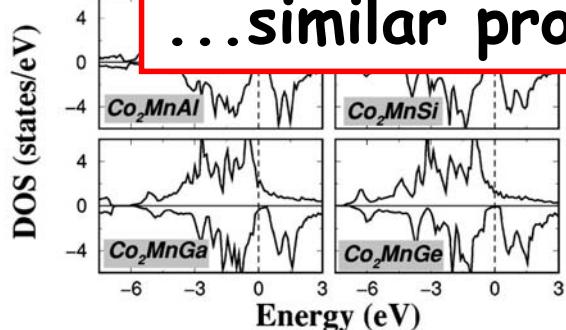
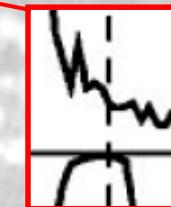


FIG. 2. Calculated spin-projected DOS for the  $\text{Co}_2\text{MnZ}$  compounds, where Z stands for Al, Ga, Si, and Ge. They all possess a finite very small spin-down DOS around the Fermi level.



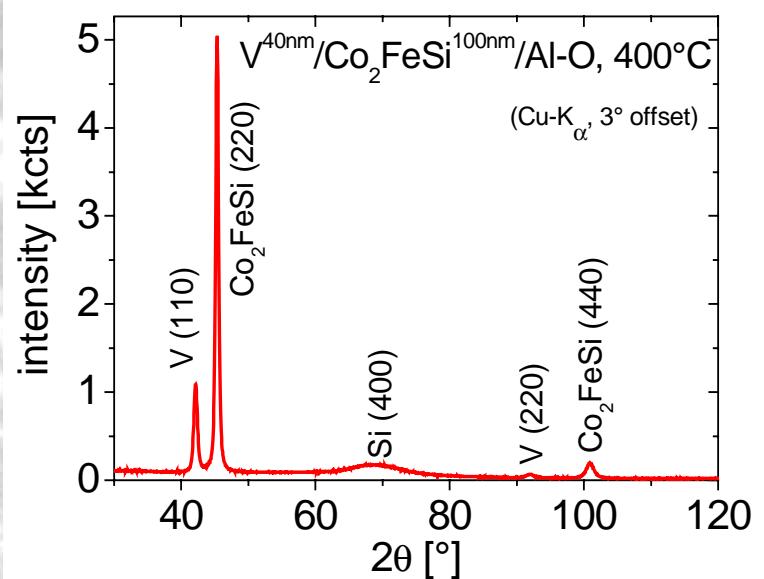
DOS( $\downarrow$ ) very small  
 $\Rightarrow$  high  $P_{\text{eff}}$  expected!

	Co	Mn	Si
$m^{\text{spin}}[\mu_B]$	1.021	2.971	-0.074
$m^{\text{orb}}[\mu_B]$	0.029	0.017	0.001

*Experiment* [J. Phys.: Con. Mat. 12 (2000) 1827]:  $M = 4.96\mu_B/\text{f.u.}$ ,  $T_C = 985\text{K}$

## ...some bulk properties of our $\text{Co}_2\text{MnSi}$ and $\text{Co}_2\text{FeSi}$ single layers and $\{\text{Co}_2\text{MnSi}/\text{Co}_2\text{FeSi}\}$ multi layers:

A) (110)-textured on V(110)-buffer



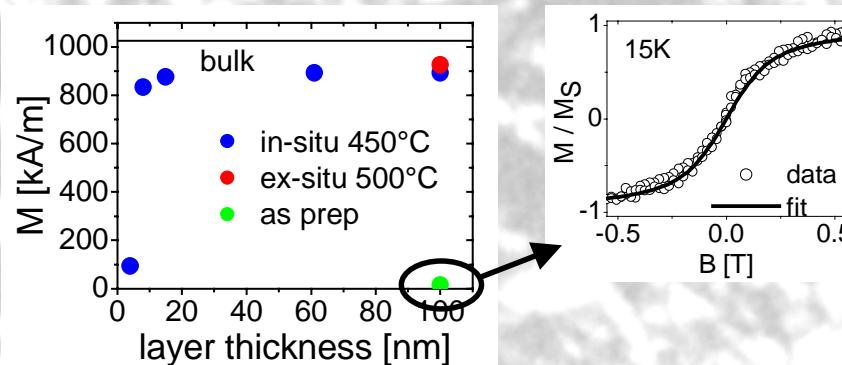
→ similar results found for  $\text{Co}_2\text{MnSi}$  single layers and  $\{\text{Co}_2\text{MnSi}/\text{Co}_2\text{FeSi}\}$  MLs

B) optimal annealed films have small coercivity at RT:  $H_c = 10\text{-}20\text{Oe}$   
→ used as "free" electrode

# ...some bulk properties of our $\text{Co}_2\text{MnSi}$ and $\text{Co}_2\text{FeSi}$ single layers and $\{\text{Co}_2\text{MnSi}/\text{Co}_2\text{FeSi}\}$ multi layers:

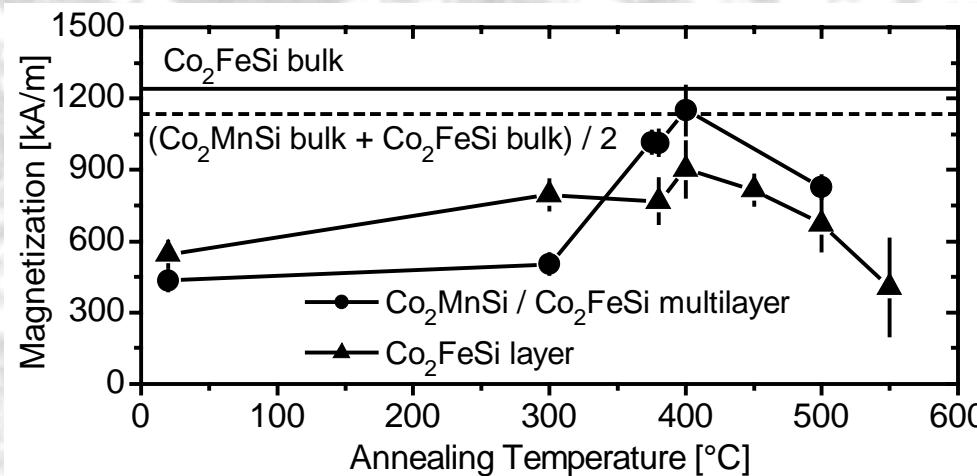
C) annealing important to induce atomic order and increase magnetization

$\text{Co}_2\text{MnSi}$  @RT:



As prepared  $\text{Co}_2\text{MnSi}$  films are superparamagnetic  
→ Langevin function:  
 $\mu \approx 300\mu_B$

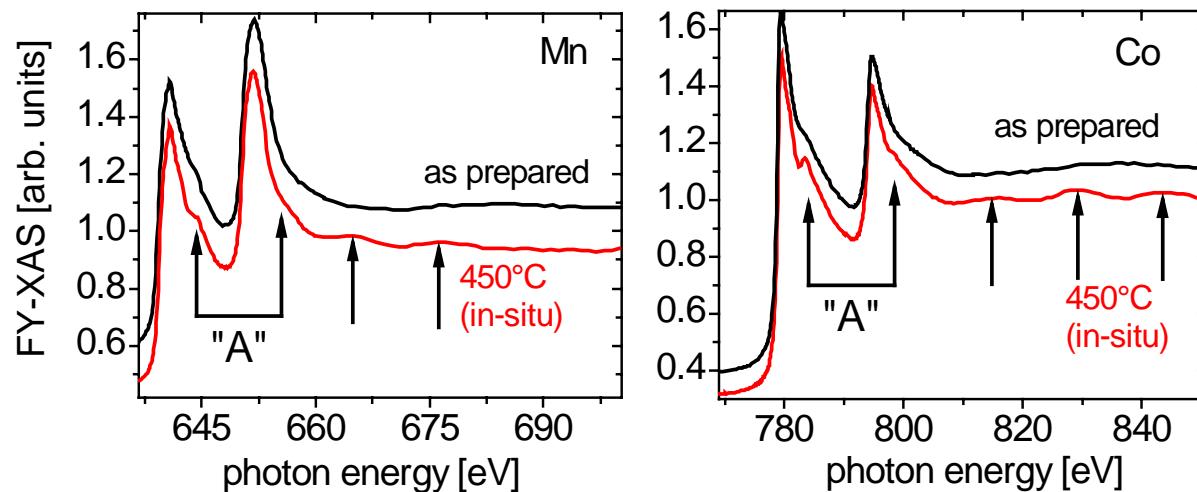
100nm thick  $\text{Co}_2\text{FeSi}$  and  $\{\text{Co}_2\text{MnSi}/\text{Co}_2\text{FeSi}\}$  @RT:



# Chemical states at $\text{Co}_2\text{MnSi}-\text{AlO}_x$ interface compared to $\text{Co}_2\text{MnSi}$ bulk (100nm):

$\text{Co}_2\text{MnSi}$  bulk:

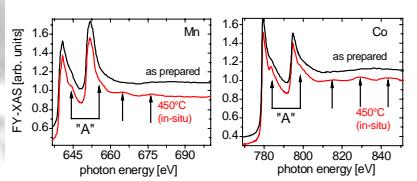
XAS at Co- and Mn- $L_{3,2}$ -edge:  $2p \rightarrow 3d$  ( $4s$ )



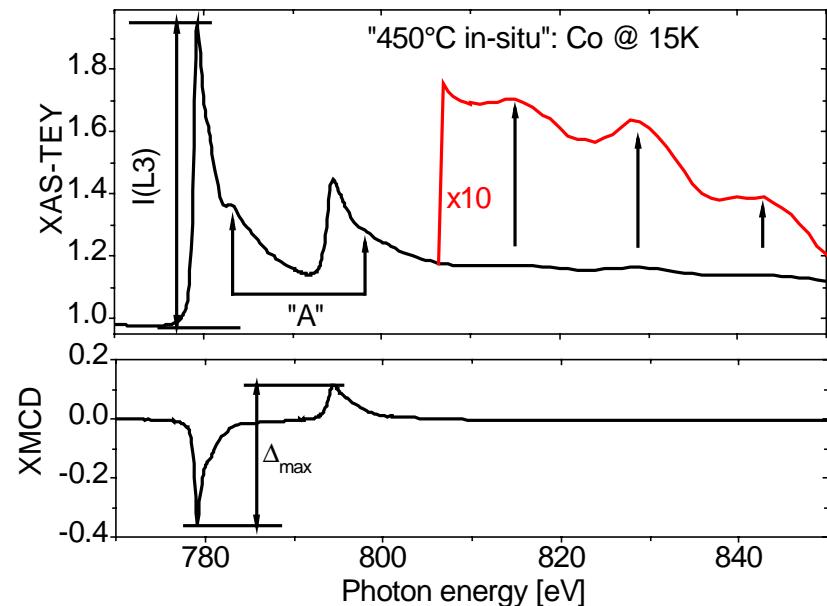
- EXAFS oscillations indicate atomic ordering
- "A": peaks in 3d-density of states 4eV above  $E_F$  (rep. by SPRKKR)  
→ annealing changes bandstructure and improves atomic order!

# Chemical states at $\text{Co}_2\text{MnSi}-\text{AlO}_x$ interface compared to $\text{Co}_2\text{MnSi}$ bulk (100nm):

$\text{Co}_2\text{MnSi}$  bulk:

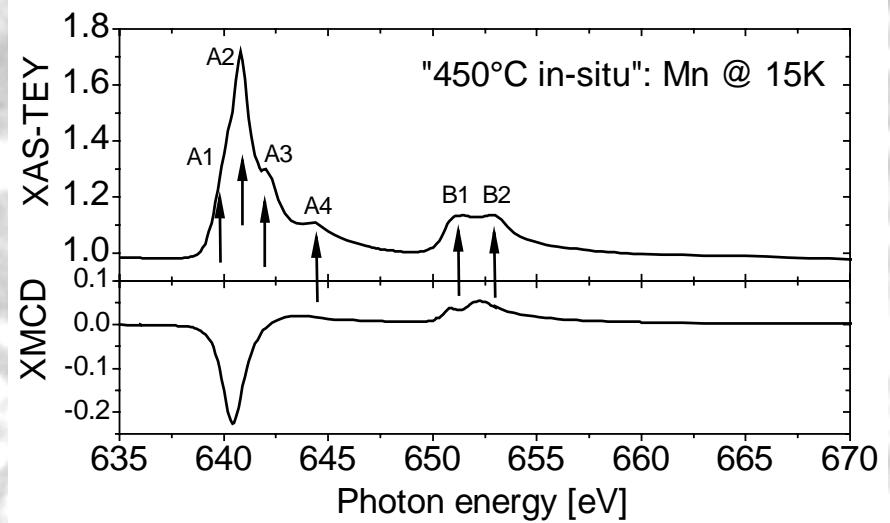


Co at  $\text{Co}_2\text{MnSi} / \text{Al-O}$  interface:



→ similar to bulk properties

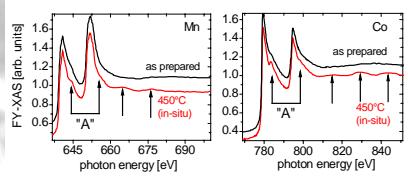
Mn at  $\text{Co}_2\text{MnSi} / \text{Al-O}$  interface:



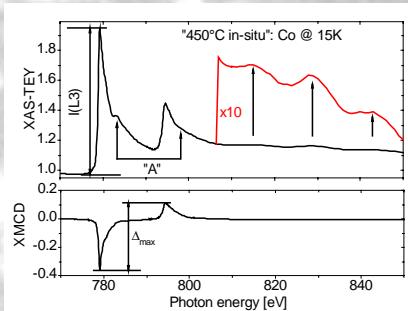
→ interfacial  $\text{MnO}$  masks finger-prints of ordering process

# Magnetic moments at $\text{Co}_2\text{MnSi}-\text{AlO}_x$ interface compared to $\text{Co}_2\text{MnSi}$ bulk (100nm):

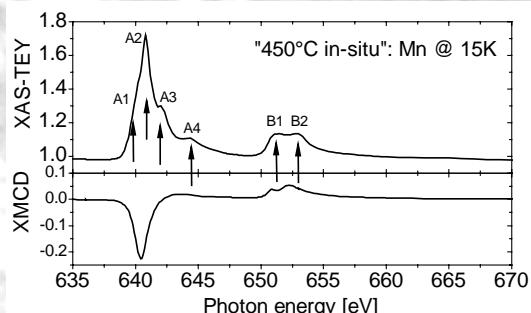
$\text{Co}_2\text{MnSi}$  bulk:



Co at  $\text{Co}_2\text{MnSi} / \text{Al-O}$  interface:



Mn at  $\text{Co}_2\text{MnSi} / \text{Al-O}$  interface:



→ Sum rules analysis<sup>[1]</sup> of TEY („450°C in-situ“):  
 $m^{\text{spin}}(\text{Mn})/m^{\text{spin}}(\text{Co}) = 1.59\mu_B/1.15\mu_B$   
 $= 1.38 < 2.9$  (theory<sup>[2]</sup>)

interfacial  $\text{MnO}$  reduces Mn moment

→ Estimation of bulk moment ratio (FY + TEY):  
 $m^{\text{spin}}(\text{Mn})/m^{\text{spin}}(\text{Co}) \approx 3$

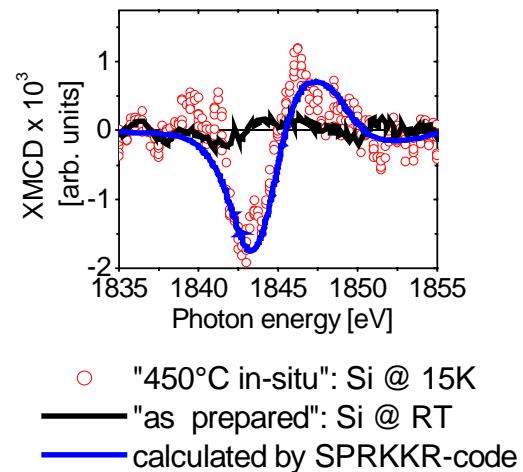
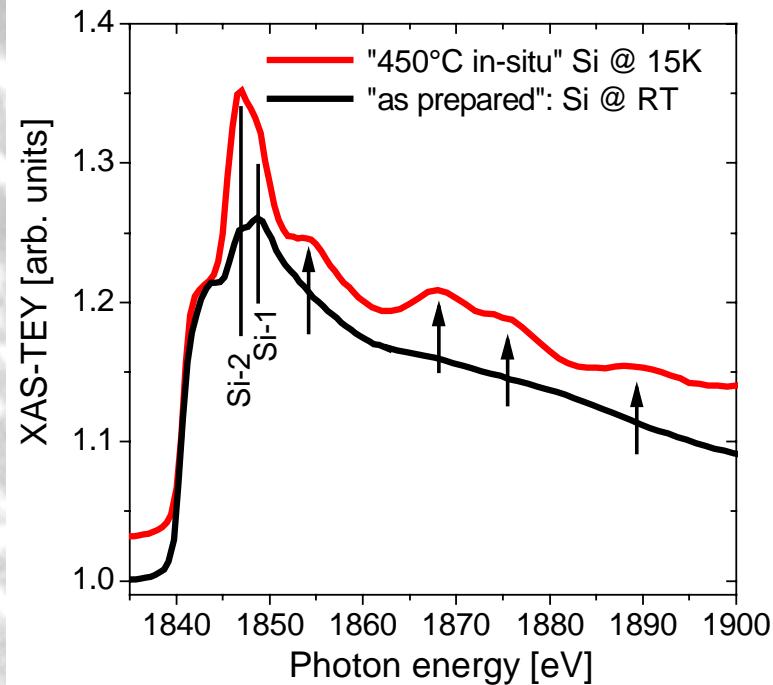
→ Temperature dependence of interfacial magnetic moments:

sample	$m(\text{LT}) / m(300\text{K})$
$\text{Co}_2\text{MnSi} / \text{Al-O}$ „as prepared“	Co: 14.0 Mn: 13.5 $\text{LT} = 15\text{K}$
$\text{Co}_2\text{MnSi} / \text{Al-O}$ „450°C in-situ“	Co: 1.06 Mn: 1.11
$\text{Co-Fe-B}/\text{Al-O}$ „275°C“	Co: 1.02 Fe: 1.03

$\Delta m/m$   
3x  
larger!

[1] Chen et al., PRL 75 (1995) 152, jj-mixing neglected  
[2] Galanakis et al., PRB 66 (2002) 174429

# Chemical and magnetic properties of Si at $\text{Co}_2\text{MnSi}-\text{AlO}_x$ interface:



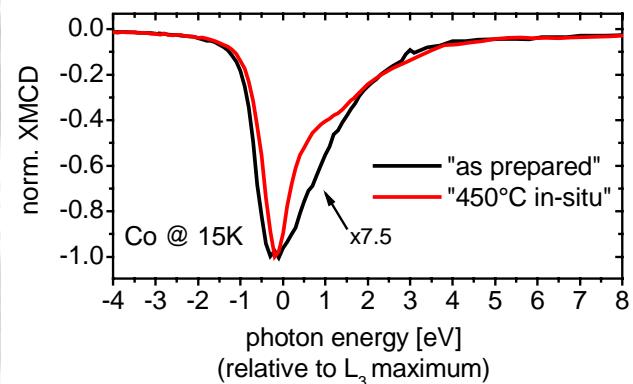
XAS at Si-K edge:  
 $1s \rightarrow 2p$

- "Si-1": interfacial  $\text{SiO}_2$  in addition to interfacial  $\text{MnO}$
- EXAFS oscillations indicate atomic ordering
- "Si-2": peak in 2p-density of states 6eV above  $E_F$  (rep. by SPRKKR)

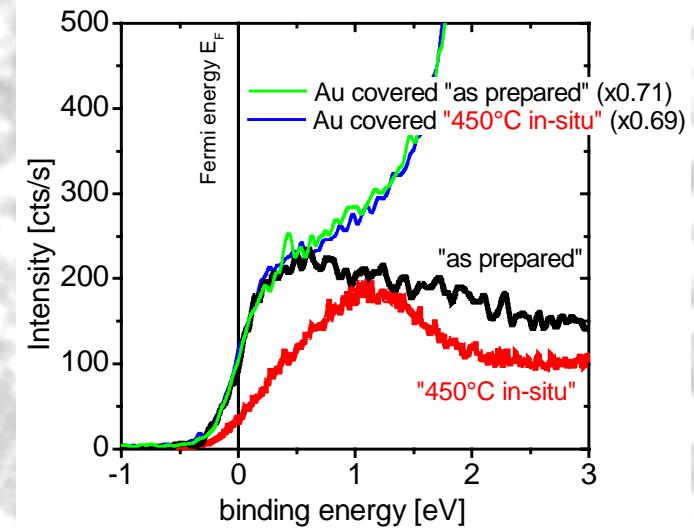
→ similar fingerprints of ordering as for Co and Mn!

...further hints to annealing induced changes of the electronic bandstructure at  $\text{Co}_2\text{MnSi}-\text{AlO}_x$  interface:

unoccupied (d-)states:



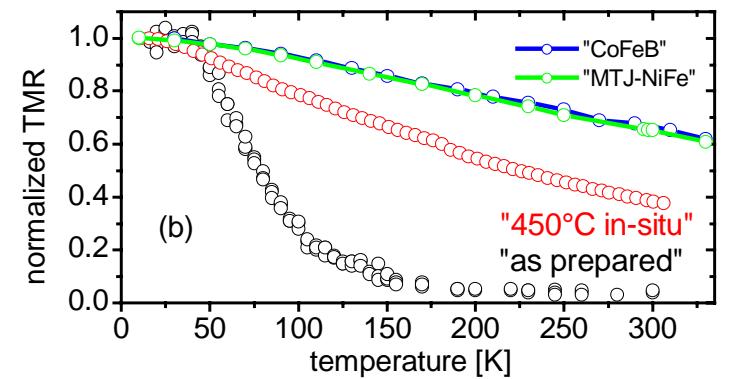
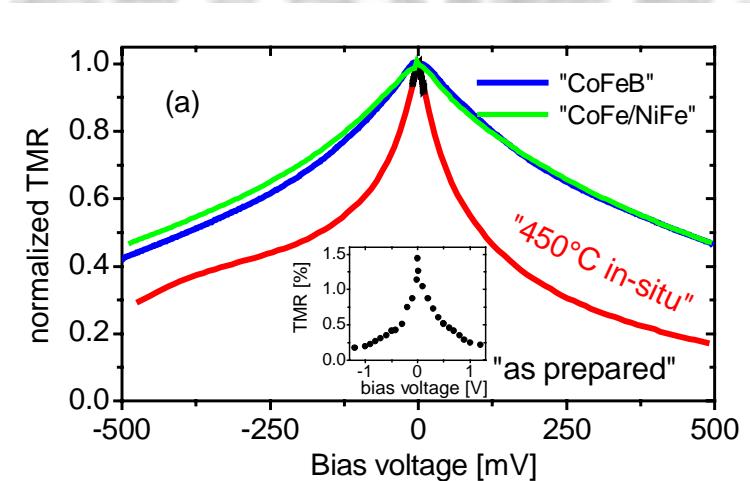
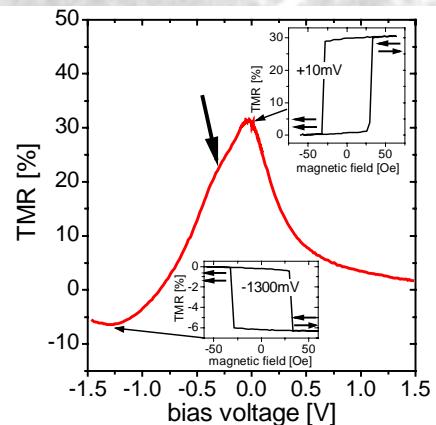
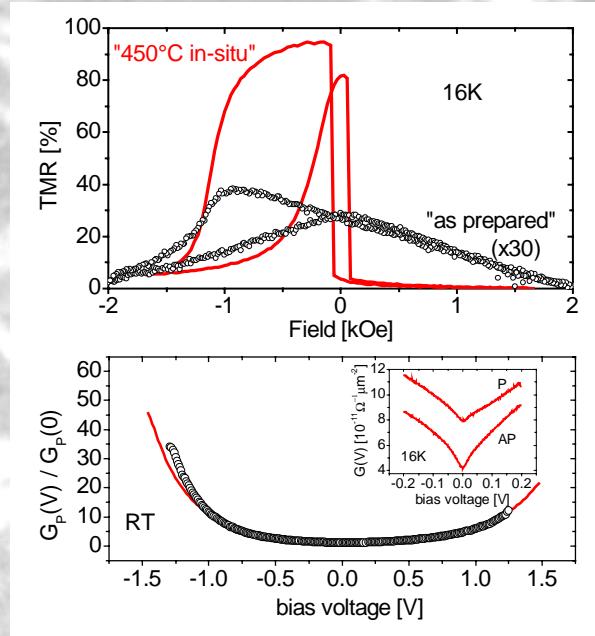
occupied states:



mono-XPS ( $h\nu=1486.7\text{ eV}$ , emission angle=  $20^\circ$ )

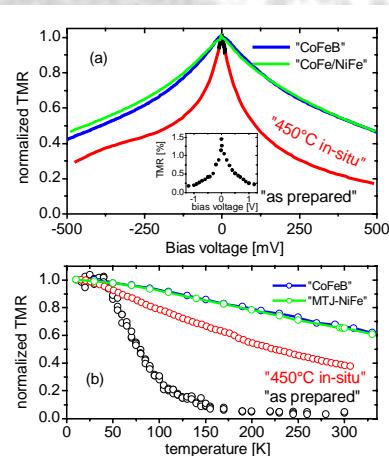
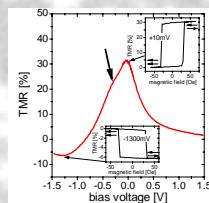
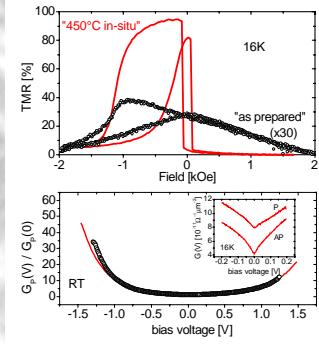
→ important for interpretation of TMR vs V dependence...

# Characteristic transport properties of $\text{Co}_2\text{MnSi}$ alloy based MTJs...



...compared with "conventional" CoFeB and NiFe/CoFe based MTJs with Al-O barrier...

# Characteristic transport properties of $\text{Co}_2\text{MnSi}$ alloy based MTJs...



→ „as prepared“ and „450°C in-situ“ have similar tunnel characteristic (similar barrier shape!)

„as prepared“:

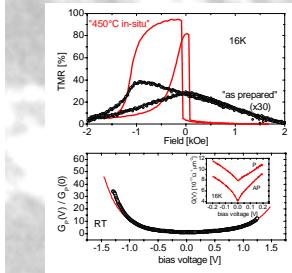
- superparamagnetic switching behavior
- strongest temperature dependence
- strongest bias voltage dependence
- TMR always positive

„450°C in-situ“:

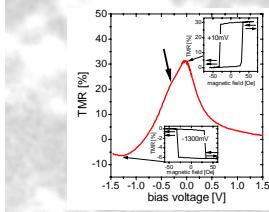
- TMR(T) convex, stronger than for „conventional“ MTJs (CoFeB, NiFe/CoFe)
- TMR(V) stronger than for „convent.“ MTJs
- negative TMR for large negative bias voltage

→ similar results are found for  $\text{Co}_2\text{MnSi}$  single layer and  $\{\text{Co}_2\text{MnSi}/\text{Co}_2\text{FeSi}\}$  ML based MTJs!

# Interpreting the transport properties of MTJs with ordered $\text{Co}_2\text{MnSi}$ electrode on the base of XAS/XMCD investigations...

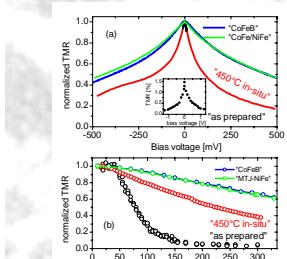


TMR inversion reflects the band structure of well ordered Heusler alloy



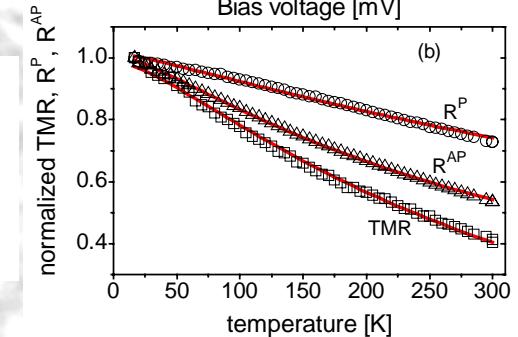
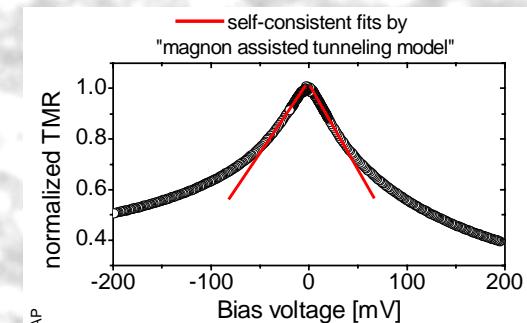
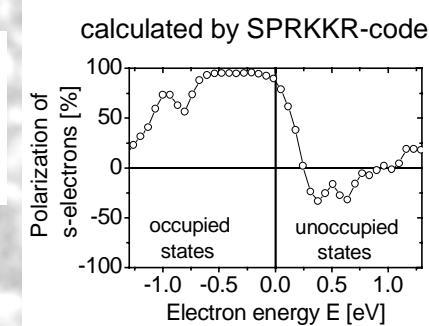
Current limitation of effective spin-polarization (66% @ 20K/1mV):

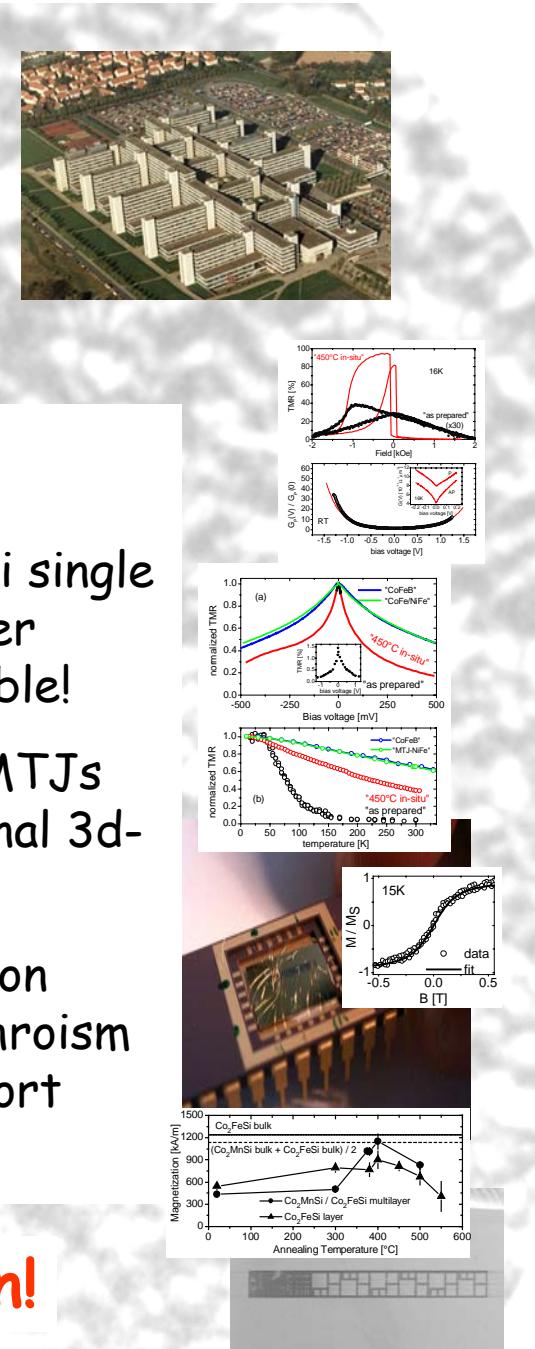
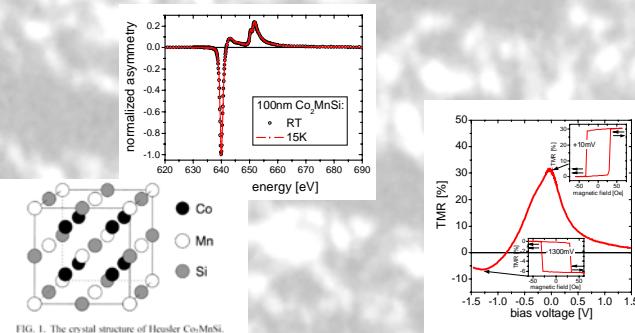
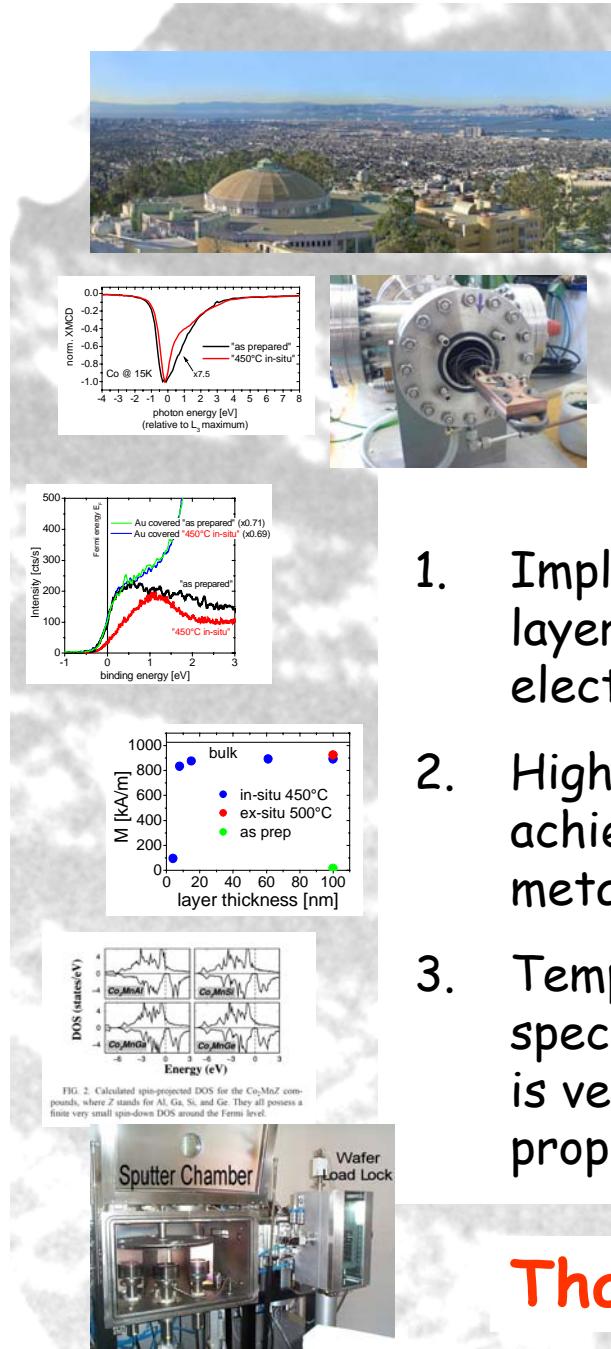
- interfacial  $\text{MnO}/\text{SiO}_2$  hinders perfect atomic order of Heusler
- spin scattering on paramagnetic  $\text{Mn}^{2+}$  ions and unpolarized conductance via defect states in the barrier (quasi-elastic processes!)



Magnon assisted tunneling<sup>[1]</sup> is suggested to be considerably stronger in "450°C in-situ" than in NiFe/Al-O/CoFe and CoFeB/Al-O/CoFeB MTJs.

[1] Han et al., PRB 63 (2001) 224404





## Conclusions

1. Implementation of Co<sub>2</sub>MnSi and Co<sub>2</sub>FeSi single layer and {Co<sub>2</sub>MnSi / Co<sub>2</sub>FeSi} multi layer electrodes in Al-O based MTJs is possible!
2. High spin-polarization of up to 0.74 in MTJs achieved, i.e., larger than for conventional 3d-metal alloy / AlO<sub>x</sub>-interfaces!
3. Temperature dependent X-ray absorption spectroscopy and magnetic circular dichroism is very useful to understand the transport properties of complex MTJ systems!

**Thank you for your attention!**